

In re Appln. of Verschueren et al.
Application No. 10/808,812

CLAIM AMENDMENTS

1. (Currently Amended) A positive working heat-sensitive lithographic printing plate precursor comprising a support having a hydrophilic surface and a coating~~s~~ provided on the hydrophilic surface, said coating comprising:

- an infrared light absorbing agent,
- an oleophilic resin soluble in an aqueous alkaline developer,
- a developer resistance means and
- spacer particles,

~~characterised in that~~ wherein said spacer particles comprise aluminum hydroxide or aluminum oxide and have an average particle size larger than 0.3 μm .

2. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said particle size is between 0.5 μm and 20 μm .

3. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said particle size is between 1 μm and 7 μm .

4. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said coating has a layer thickness comprised between 0.6 g/m^2 and 2.8 g/m^2 .

5. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said coating comprises at least two layers and wherein said spacer particles are present in at least one of the layers of the coating.

6. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein the amount of said particles in the coating is between 5 and 200 mg/m^2 .

7. (Original) A positive working heat-sensitive lithographic printing plate precursor according to claim 1 wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

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8. (Original) A stack comprising a plurality of positive working heat-sensitive lithographic printing plate precursors, according to claim 1, wherein adjacent plate precursors are separated by an interleave.

9. (Original) A package comprising a stack according to claim 8.

Claim 10 (Canceled)

11. (New) A process for improving the scuff-mark resistance of a positive working heat-sensitive lithographic printing plate precursor comprising providing a support having a hydrophilic surface and applying onto the hydrophilic surface of the support a coating comprising:

- an infrared light absorbing agent,
- an oleophilic resin soluble in an aqueous alkaline developer,
- a developer resistance means and
- spacer particles,

wherein said spacer particles comprise aluminum hydroxide or aluminum oxide and have an average particle size larger than 0.3 μm .

12. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 2, wherein said coating has a layer thickness comprised between 0.6 g/m^2 and 2.8 g/m^2 .

13. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 12, wherein said coating comprises at least two layers and wherein said spacer particles are present in at least one of the layers of the coating.

14. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 13, wherein the amount of said particles in the coating is between 5 and 200 mg/m^2 .

15. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 14, wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

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16. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 3, wherein said coating has a layer thickness comprised between 0.6 g/m^2 and 2.8 g/m^2 .

17. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 16, wherein said coating comprises at least two layers and wherein said spacer particles are present in at least one of the layers of the coating.

18. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 17, wherein the amount of said particles in the coating is between 5 and 200 mg/m^2 .

19. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 18, wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.

20. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 5, wherein the amount of said particles in the coating is between 5 and 200 mg/m^2 .

21. (New) A positive working heat-sensitive lithographic printing plate precursor according to claim 20, wherein said developer resistance means is a polymer comprising siloxane or perfluoroalkyl units.